## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

in re Application of:		)	Examiner: P. B. Kim
Kazuo IIZUKA et al.		:	C
		) :	Group Art Unit: 2851
Application No.: 10/762,481		)	Confirmation No.: 4938
Filed: January 23, 2004		:	
		)	Allowed: September 7, 2006
		•	
For:	PROJECTION EXPOSURE	)	September 22, 2006
	APPARATUS	•	

## Mail Stop Issue Fee

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

## STATEMENT REGARDING SUBSTANCE OF THE INTERVIEW

Sir:

Applicants wish to thank the Examiner for the courtesies extended toward their representative during a telephone conversation of August 21, 2006, which was reported in the Interview Summary dated August 24, 2006, in the above-identified application. The Examiner and Applicants' representative discussed that the invention is directed to the exposure of a large substrate with repeated exposure by moving the member n times the pitch of the column, where n is less than the number of columns. The Examiner agreed to reconsider the rejection based on Applicants' explanation.

Applicants' undersigned representative may be reached in our Washington, D.C. office by telephone at (202) 530-1010. All correspondence should continue to be directed to our below-listed address.

Respectfully submitted,

Attorney for Applicants

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